

FIG.1
PRIOR ART

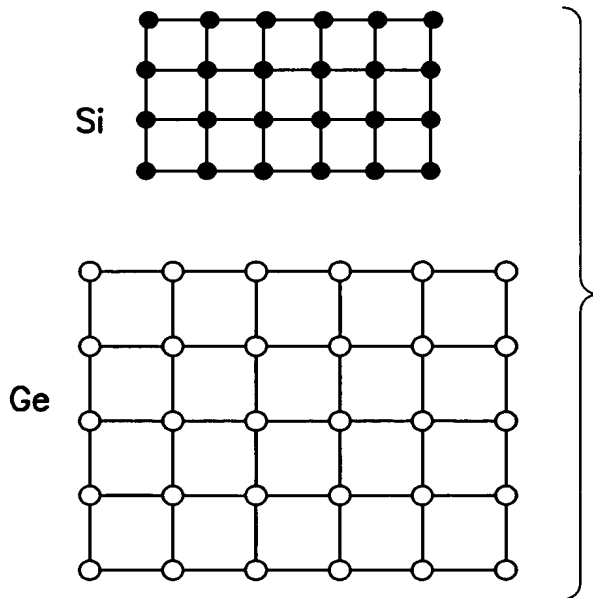


FIG.2a
PRIOR ART

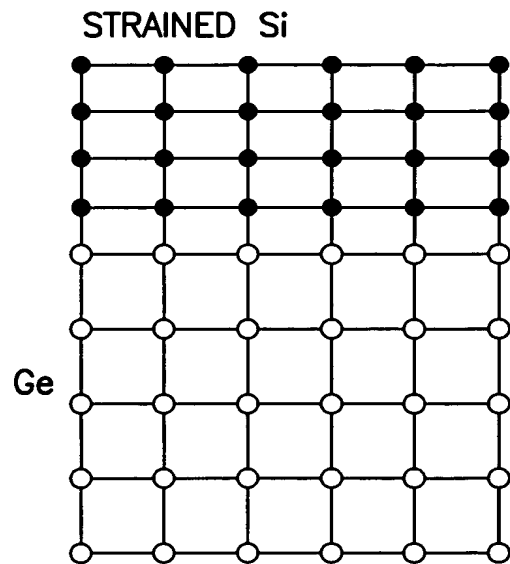


FIG.2b
PRIOR ART



<u>38</u>	SILICON
<u>22</u>	BURIED OXIDE LAYER (BOX)
<u>20</u>	SUBSTRATE

FIG.5a

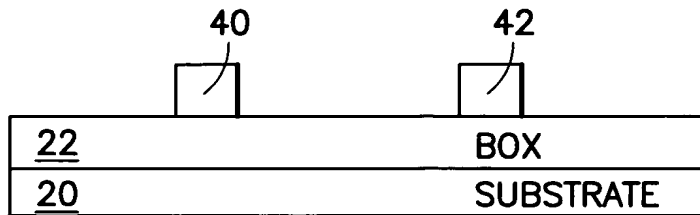


FIG.5b

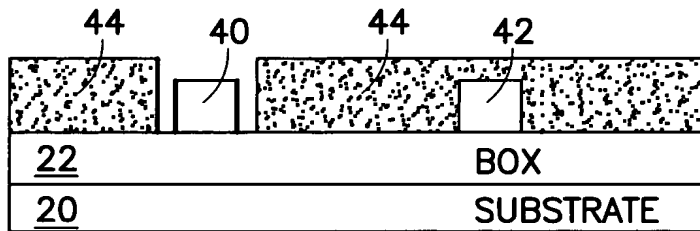


FIG.5c

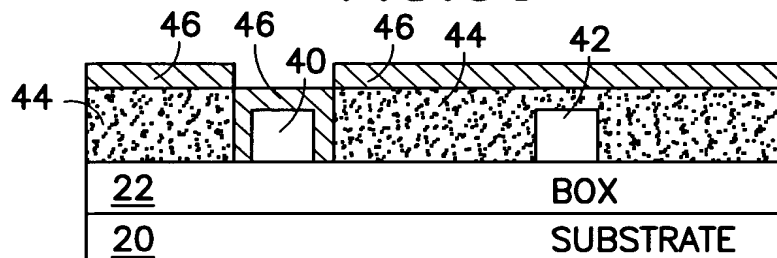


FIG.5d

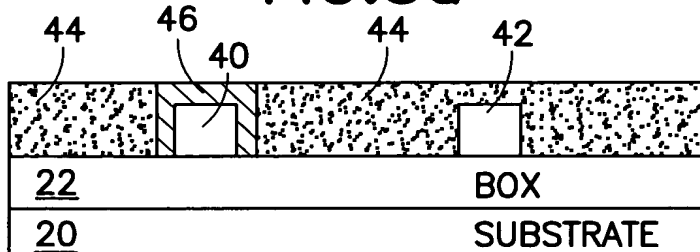


FIG.5e

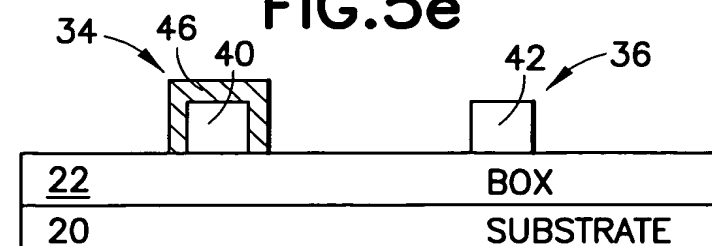


FIG.5f

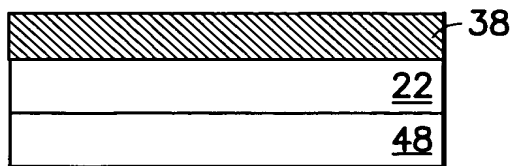


FIG. 6a

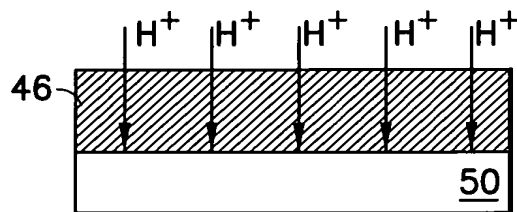


FIG. 6c

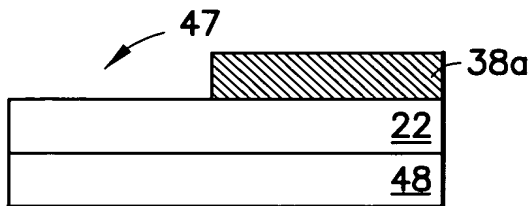


FIG. 6b

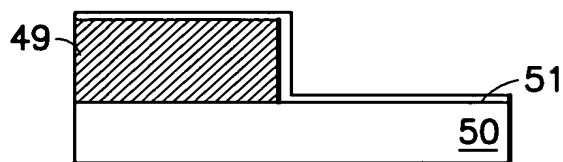


FIG. 6d

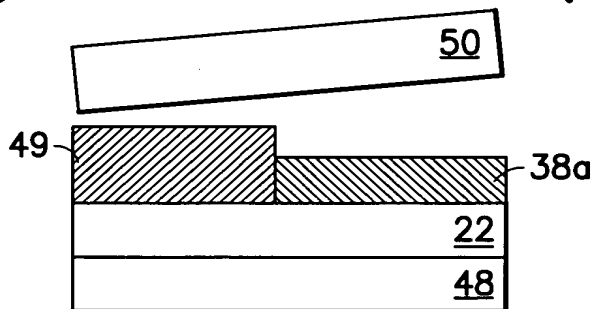


FIG. 6e

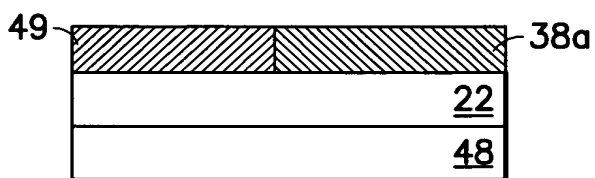


FIG. 6f

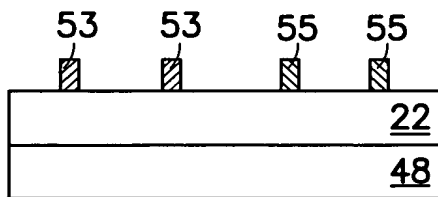


FIG. 6g

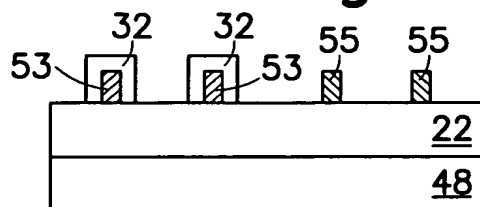


FIG. 6h

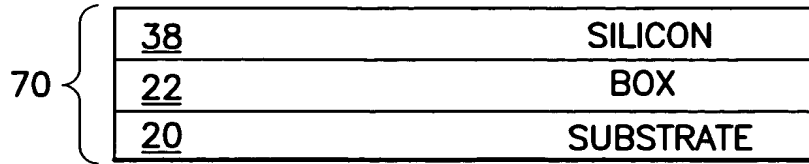


FIG.7a

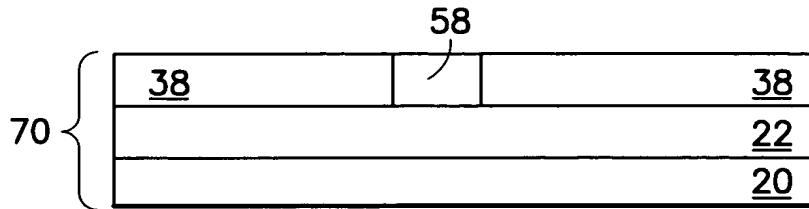


FIG.7b

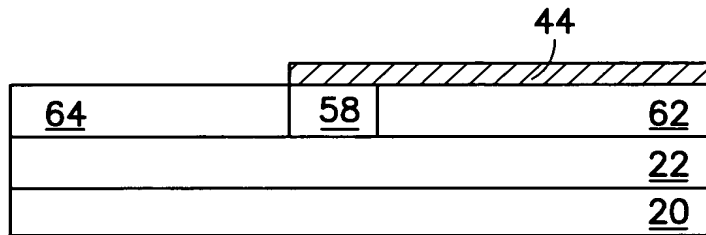


FIG.7c

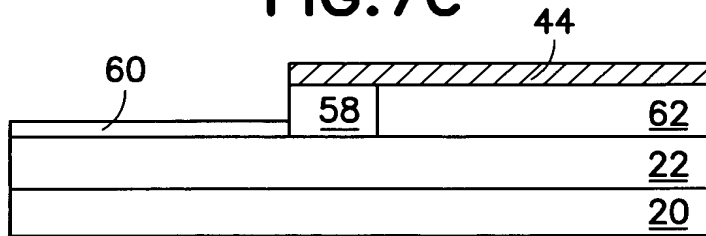


FIG.7d

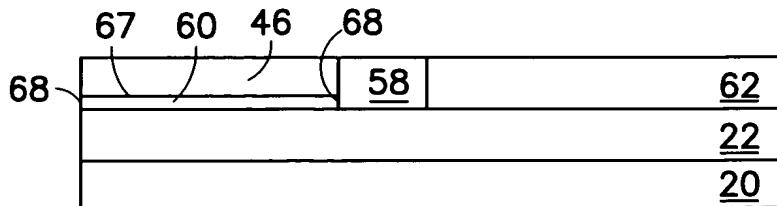
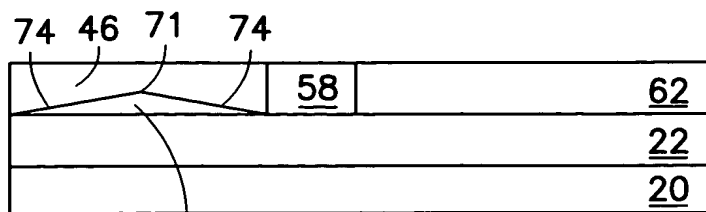


FIG.7e



75 FIG.7f

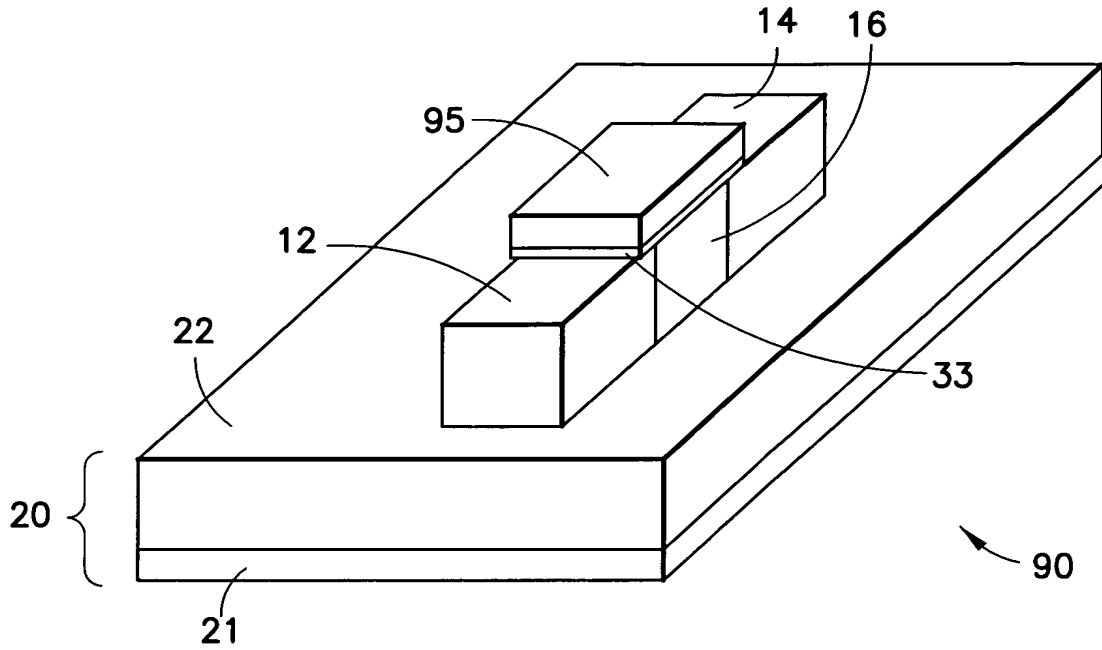


FIG. 8A

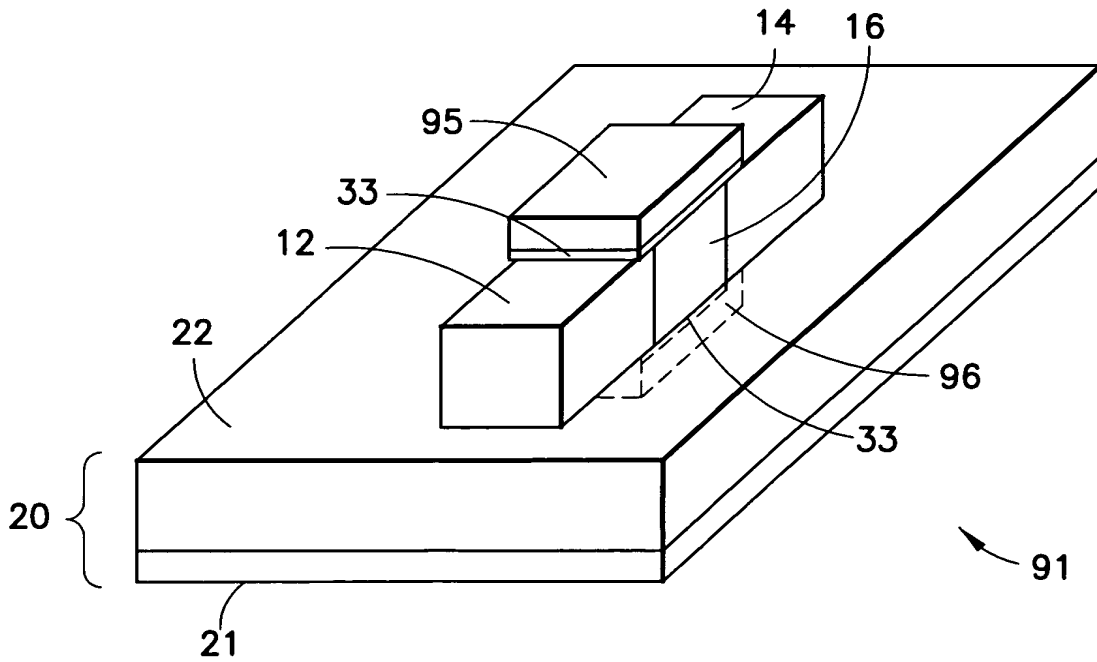


FIG. 8B

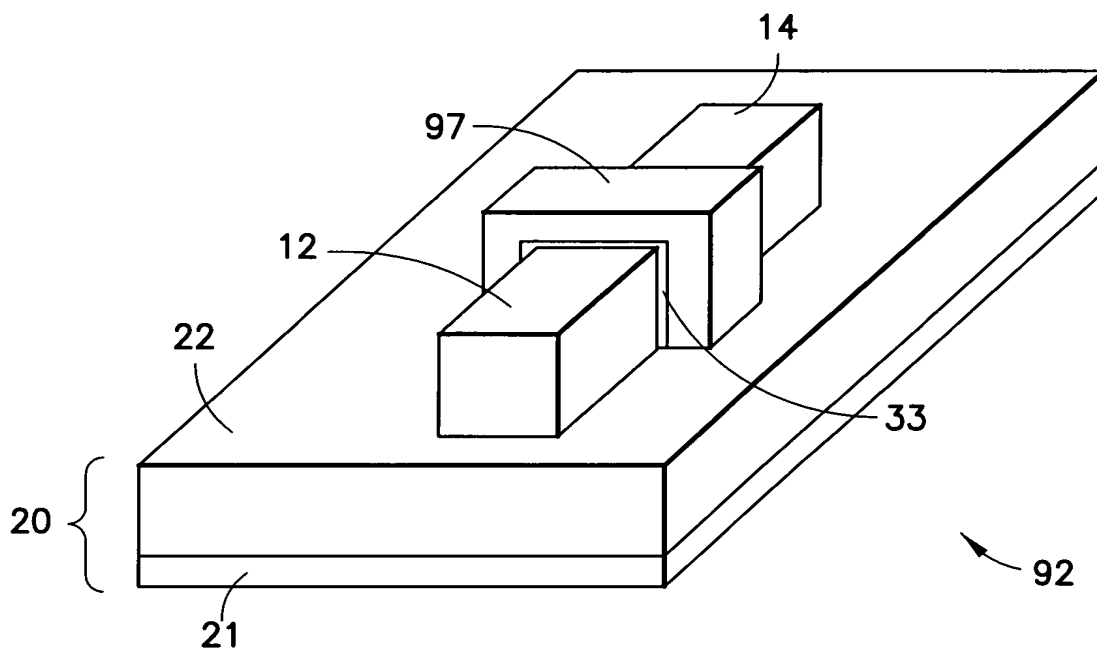


FIG. 8C

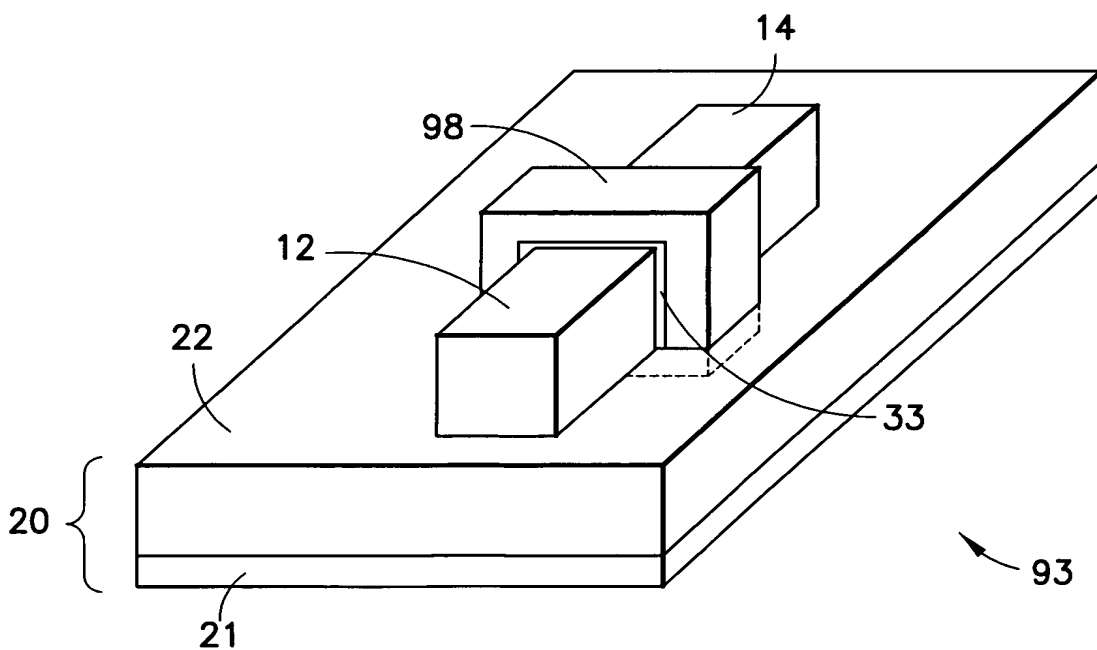


FIG. 8D

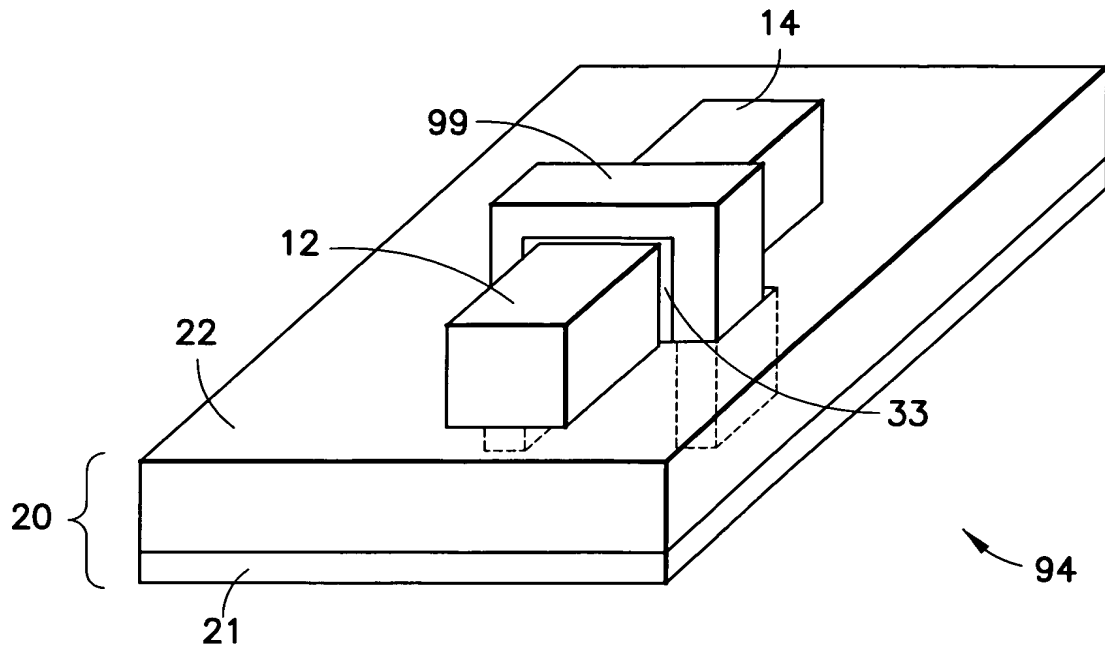


FIG. 8E

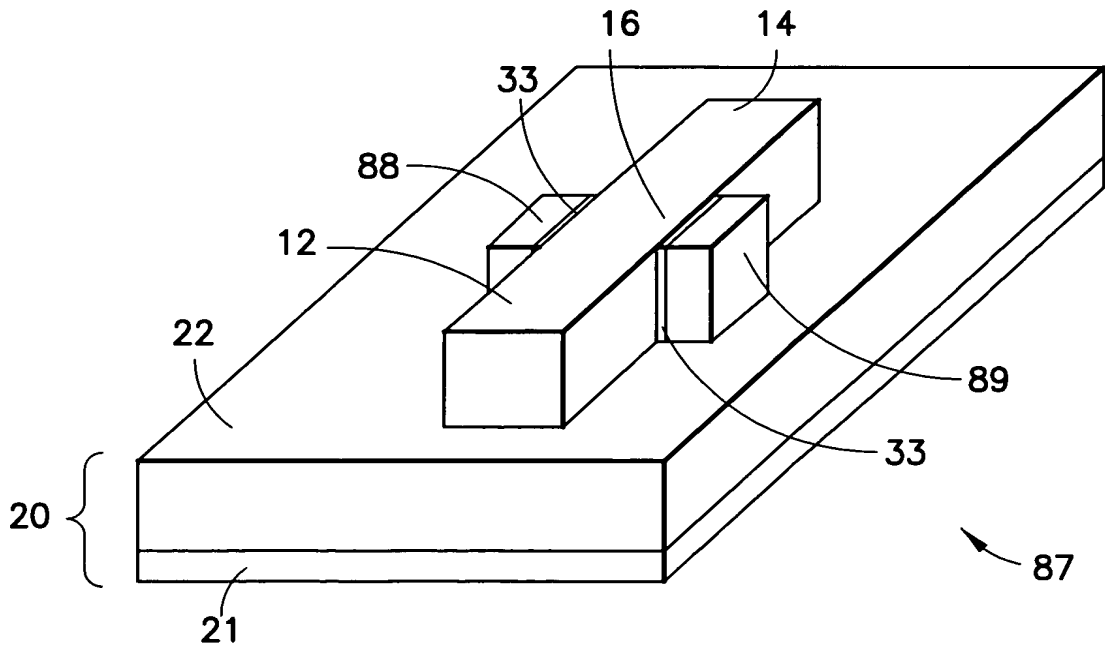


FIG. 8F

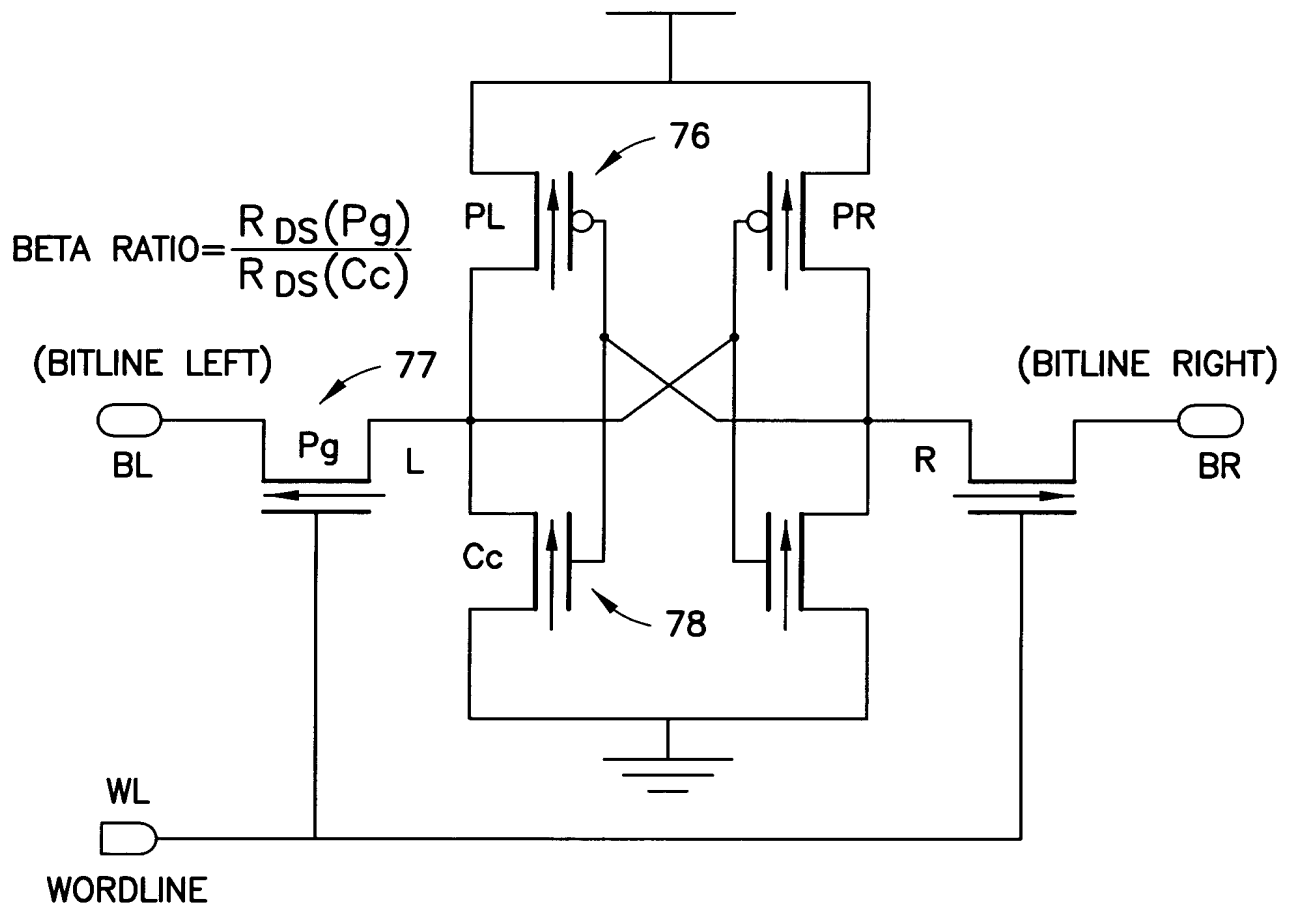


FIG.9